



MIT LINCOLN LABORATORY

microsystems
prototyping foundry

MPF

MPF specs

- 18,000-square-foot ISO 4 (Class 10) cleanroom
- 5 projection lithography platforms, including 193 nanometer
- More than 100 process tools
- 24-hour operation 5 days a week
- Custom circuits in multiple technologies

inside the MPF PROCESS EQUIPMENT LAYOUT

Located at MIT Lincoln Laboratory, 244 Wood St., Lexington, MA 02421-6426



Chemical mechanical polishing

Photolithography

Metrology

Etch

Thin films

Ion implant

Diffusion

**THE MOST
ADVANCED**

U.S. GOVERNMENT
MICROELECTRONICS
FOUNDRY



*Do you **need to access tools** for fabricating microelectronics?*

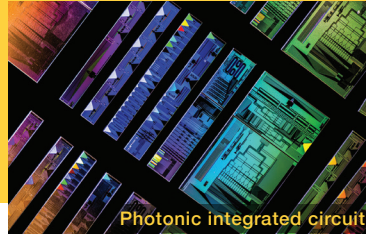
Lincoln Laboratory's 90-nanometer semiconductor research and fabrication facility is the U.S. government's most capable foundry. Unlike other foundries, we specialize in customization. Our experts can tailor a fabrication process to fit your design's needs, work with you to fabricate a full device, or grow just a single epitaxial layer. You can take advantage of our 200-millimeter wafer fabrication processes and services through a test agreement with our laboratory.

features

- 90-nanometer CMOS toolset for processing on 200-millimeter wafers
- 193-, 248-, and 365-nanometer lithography
- 4-nanometer electron beam writing
- Molecular-beam epitaxy
- DMEA Category 1A Trusted Design, Aggregation, Foundry Services, Post Processing, and Packaging/Assembly accreditation and ISO 9001:2015 certification



A technician inspects a wafer

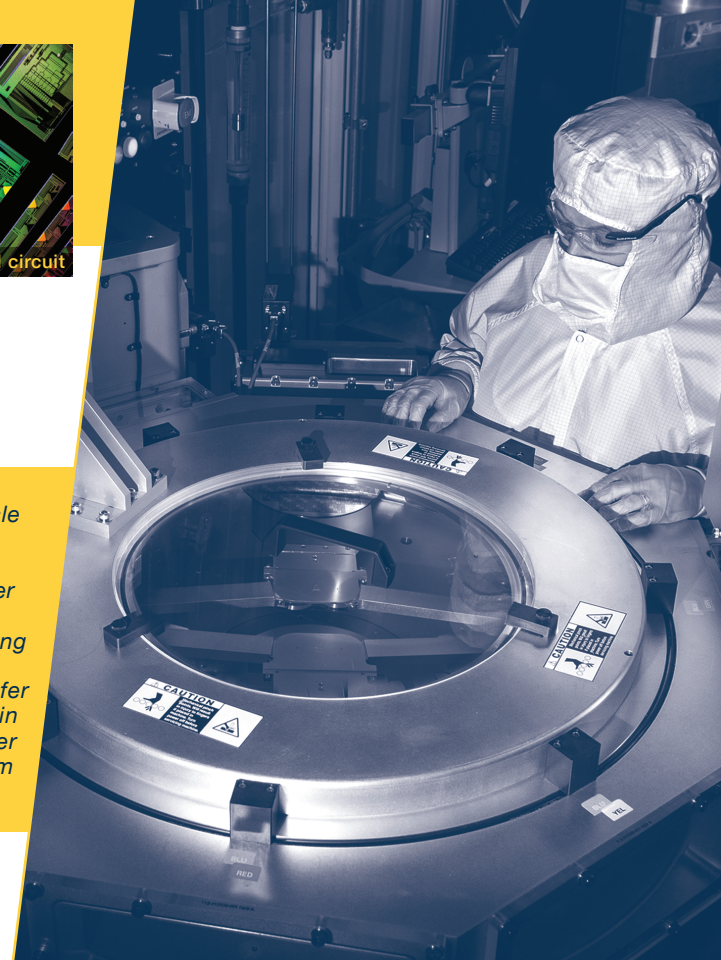


Photonic integrated circuit



At left: A reticle is loaded into a pod for 193-nanometer lithography wafer patterning

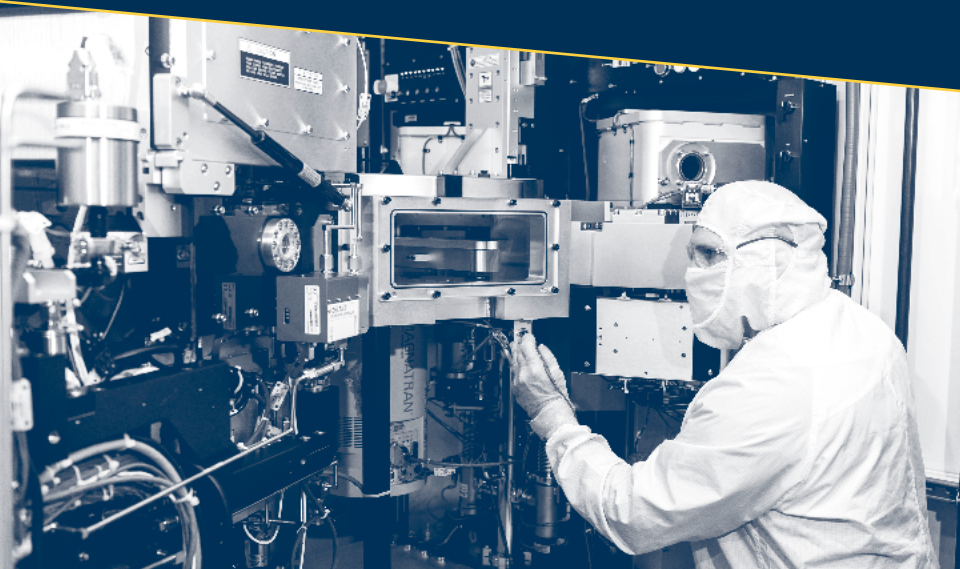
At right: A wafer is transferred in a multichamber cluster vacuum system



interested?

Contact us at MEL.Director@ll.mit.edu

Information on how to engage in a test agreement is at
www.ll.mit.edu/testagreements





WWW.LL.MIT.EDU



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